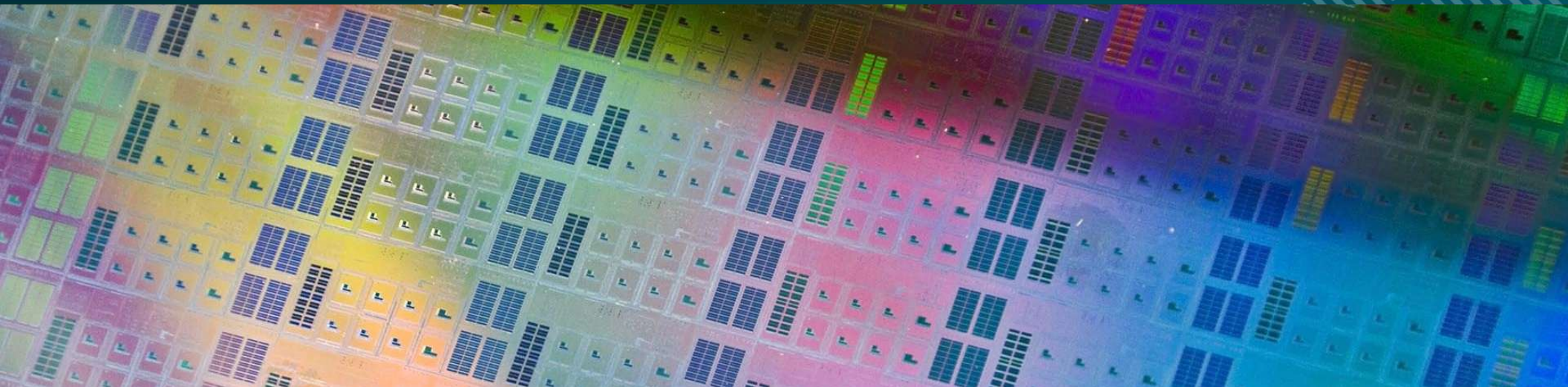


Introduction to Grazing Incidence and X-Ray Reflectivity

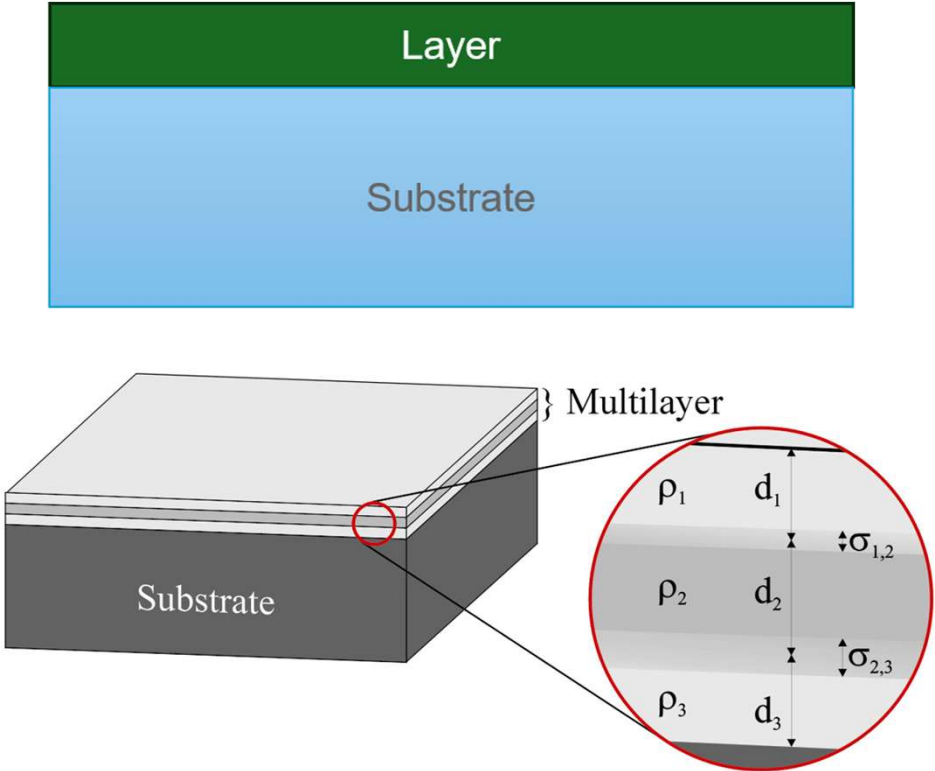
Brad Losey, PhD



Introduction to Thin Films

Structure

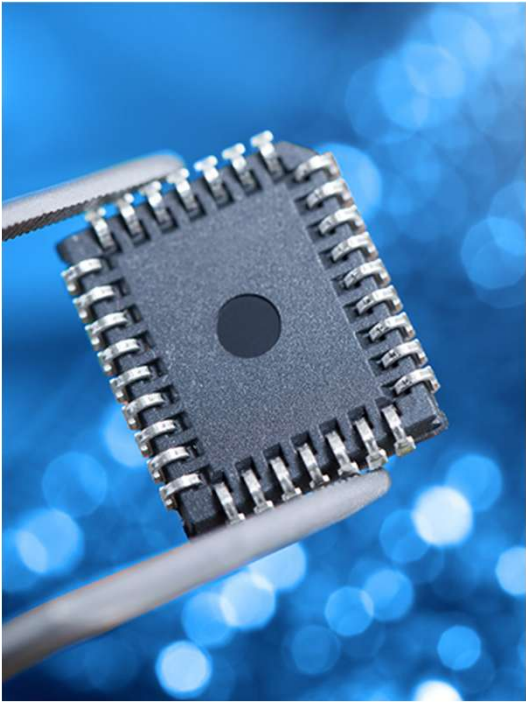
- Characteristics
 - Nanometers to microns thick
 - Used to impart specific electrical, optical, magnetic, or mechanical properties.
- Substrate:
 - Used to control the deposition of the “active” layer(s).
 - Material chosen is based on cost, flatness, rigidity, thermal & electrical conductivity, offcut, etc.
 - Can be single crystal, polycrystalline, amorphous.
 - If there is a crystallographic relationship between the layer and substrate, it is epitaxial.
- Layer:
 - Usually metallic or semiconducting
 - Can be multi-layered



Introduction to Thin Films

Applications

- Microelectronics and Semiconductors
 - Microchips
 - Integrated Circuits
 - Sensors
 - Transistors
 - Displays
- Optics and Photonics
 - Anti-Reflective Coatings
 - Mirrors
 - Optical Filters
- Energy Generation and Storage
 - Photovoltaics
 - Batteries
- Protective Coatings
 - Wear Resistance
 - Biomedical Implants



Introduction to Thin Films

Measurement Techniques



- **Grazing incidence (GI-XRD)**
 - Utilized for phase identification, residual stress, texture, crystallite size/strain and depth profiling
 - Generally restricted to polycrystalline films
 - Parallel beam geometry with a point detector
- **X-ray Reflectivity (XRR)**
 - Utilized to obtain density, thickness and roughness (surface and interface)
 - Can be applied to single crystal, polycrystalline and amorphous films
 - Parallel beam geometry/high-resolution optics with a point detector

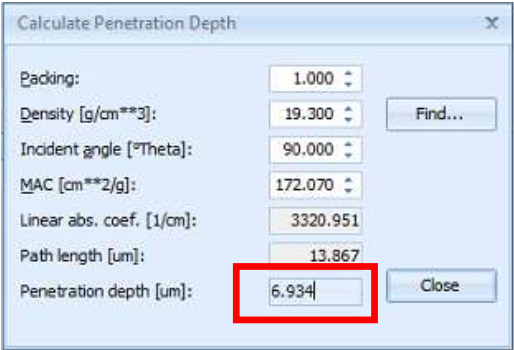
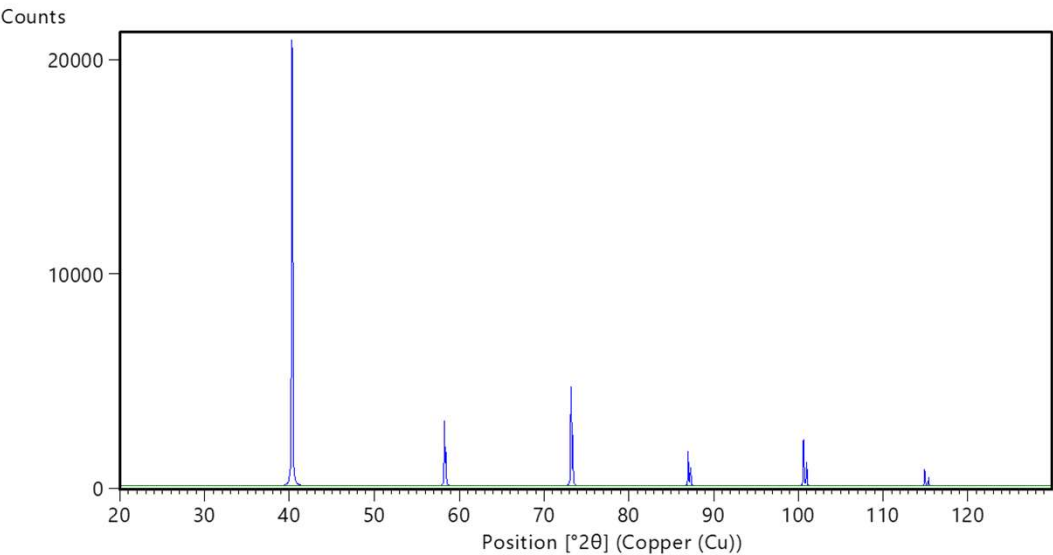
Introduction to Thin Films

Thickness Considerations



- With this film material and thickness, only the top layer will be observed

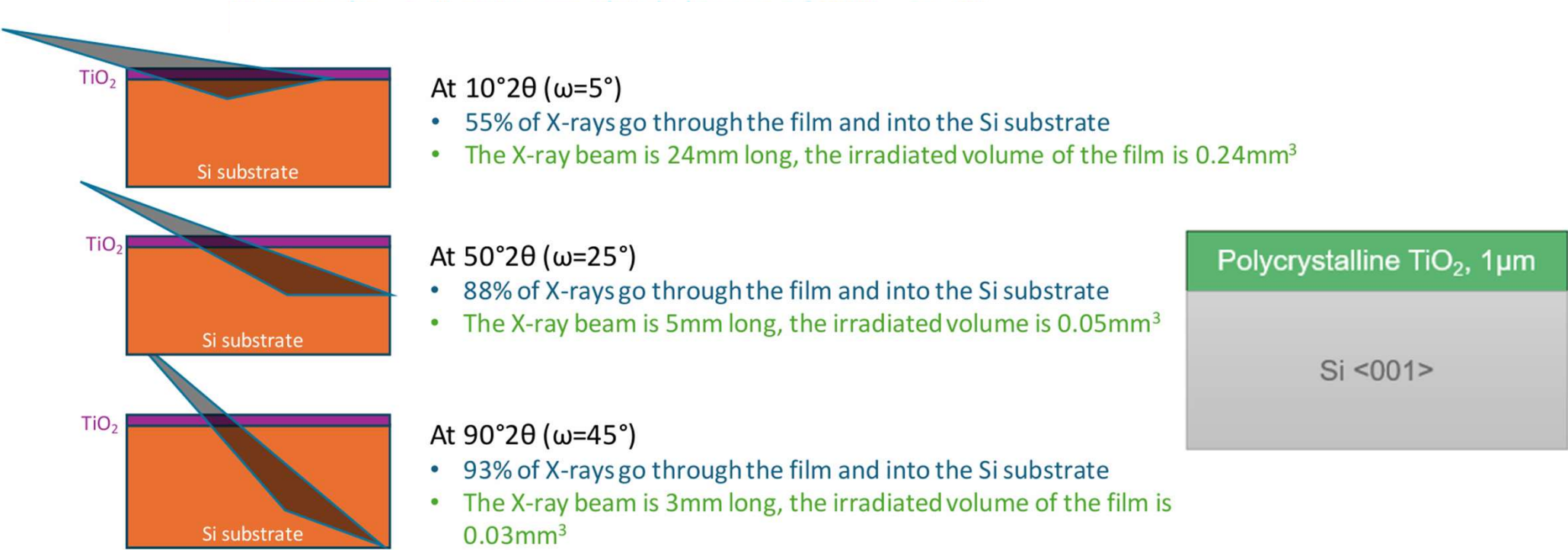
Single-phase, tungsten layer



This means it is single crystal silicon with the <001> direction perpendicular to the surface

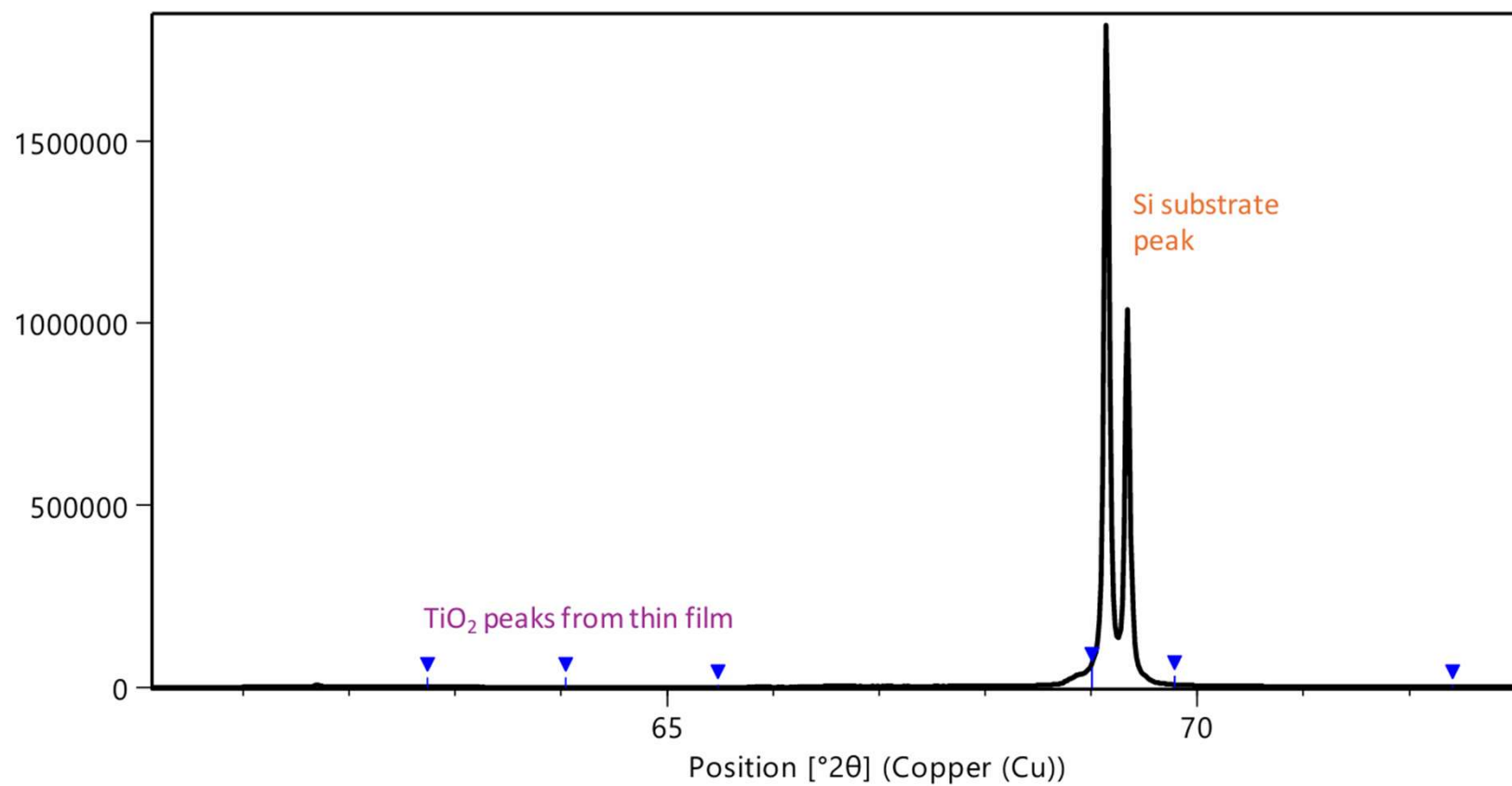
Introduction to Grazing Incidence

X-Ray Penetration Depth



Introduction to Grazing Incidence

Film Intensity

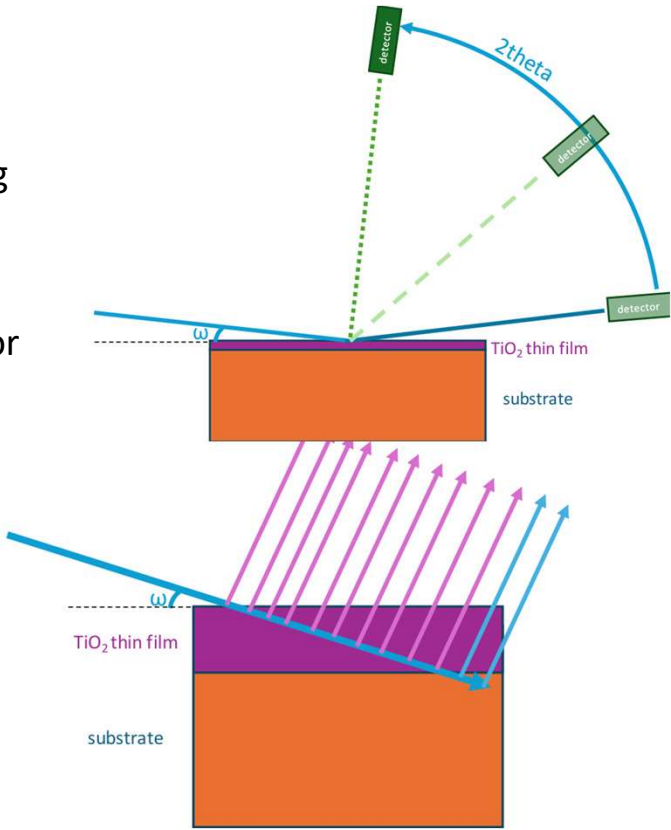
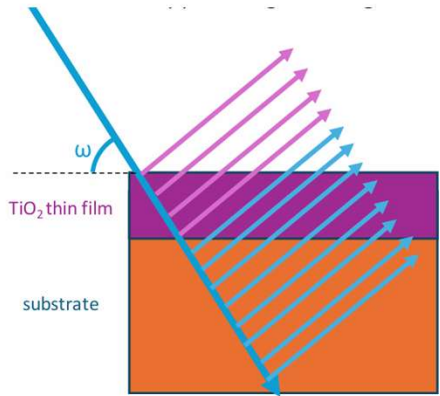
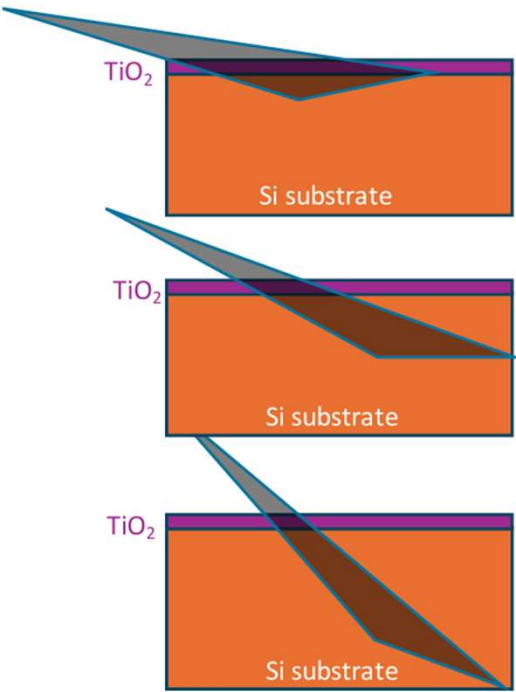


Introduction to Grazing Incidence

Utilizing Fixed Incidence Angles



- Incident beam held at a fixed low angle
- Improves scattering intensity from the film
- Asymmetric geometry breaks the diffracting condition for single crystals
- Constant beam footprint
- X-ray penetration depth can be controlled or varied for depth profiling



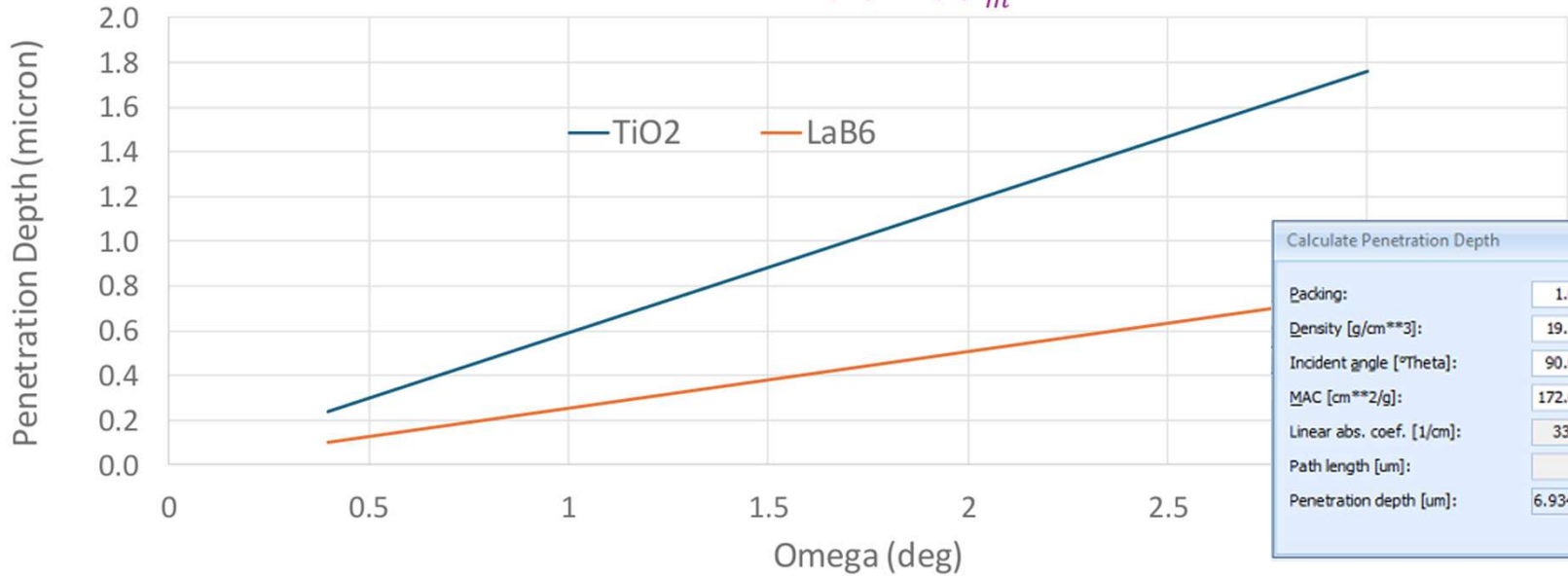
Introduction to Grazing Incidence

Penetration Depth and Film Composition



Depth of penetration calculations vary depending on what % of the X-ray beam you assume is scattered. The plots shows penetration depth calculated for 99.9% X-rays scattered ($I_L/I_0=0.001$)

$$T = 0.5 * \sin(\omega) * \ln\left(\frac{I_L}{I_0}\right) * \left(\frac{\mu}{\rho}\right)_m * \rho_m$$



Calculate Penetration Depth

Packing:

1.000

Density [g/cm**3]:

19.300

Incident angle [°Theta]:

90.000

MAC [cm**2/g]:

172.070

Linear abs. coef. [1/cm]:

3320.951

Path length [um]:

13.867

Penetration depth [um]:

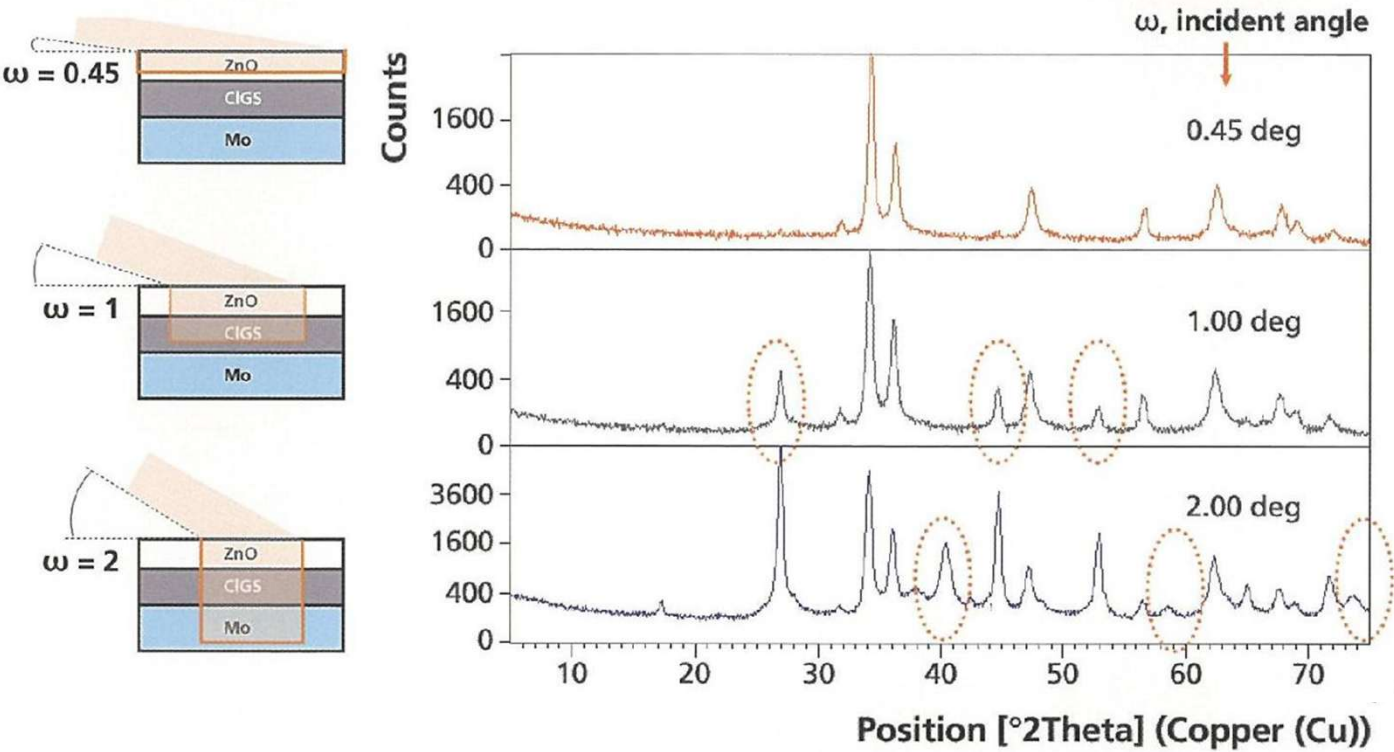
6.934

Find...

Close

Introduction to Grazing Incidence

Depth Profiling

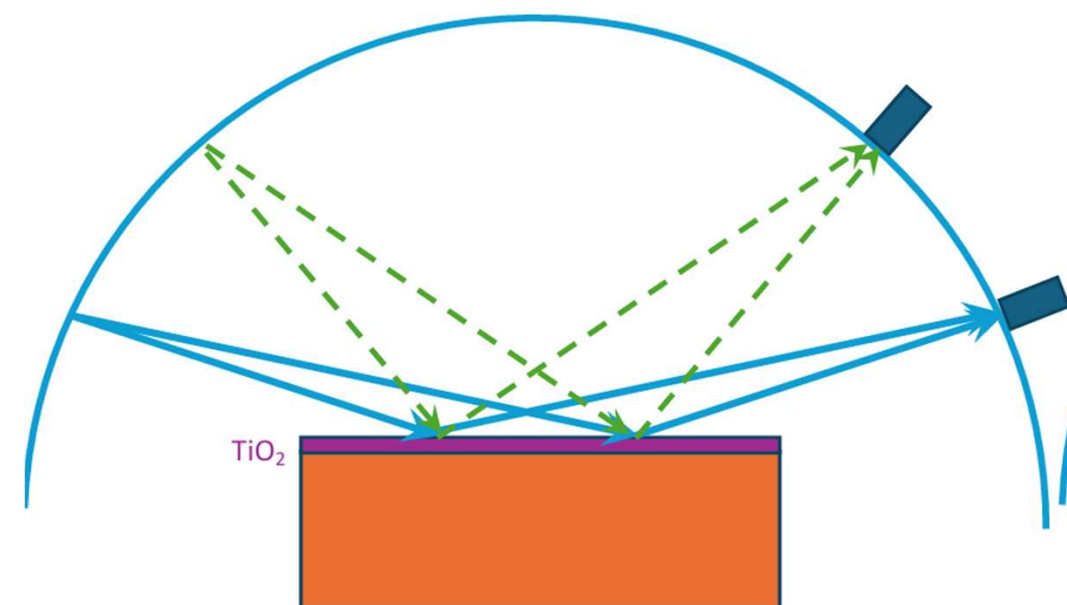


Example of depth profiling on a CIGS solar structure, showing the different layers exposed to a parallel X-ray beam in a sequential mode by varying the incident angle.

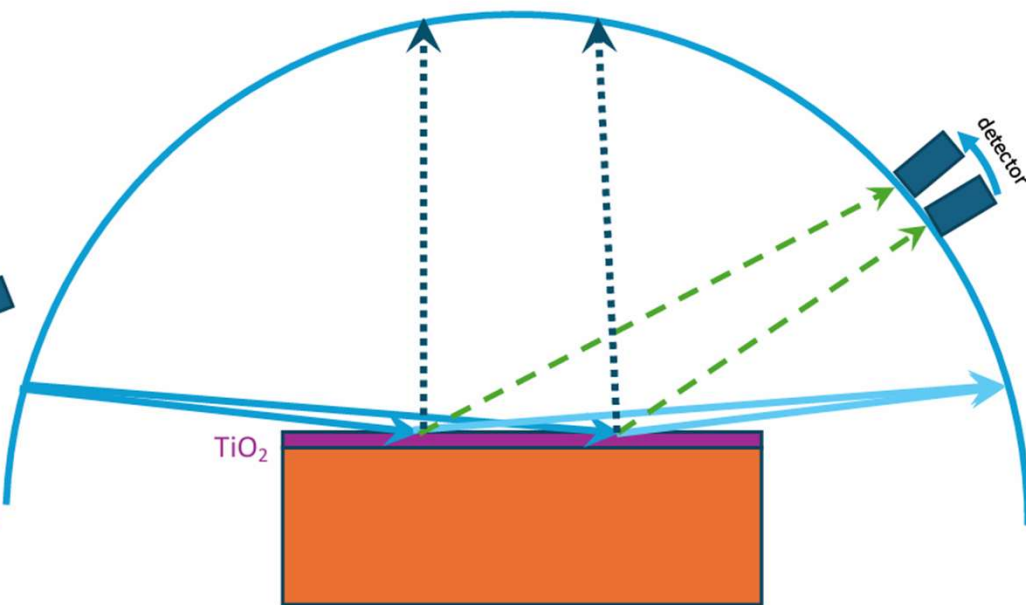
Introduction to Grazing Incidence

Defocusing Effects

Bragg-Brentano



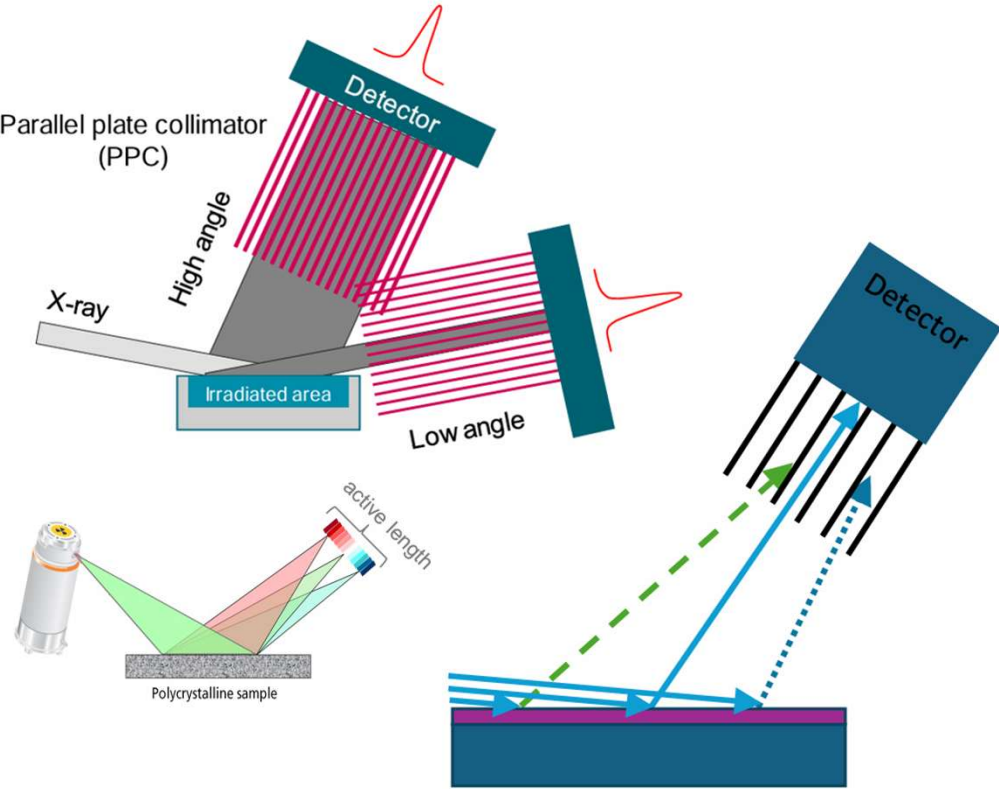
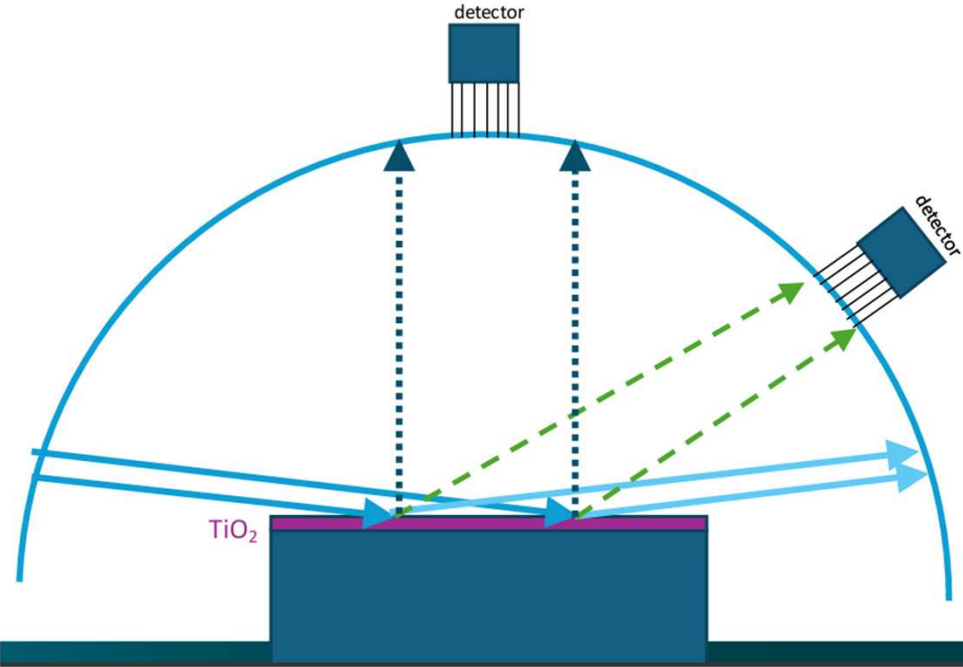
Grazing Incidence



Introduction to Grazing Incidence

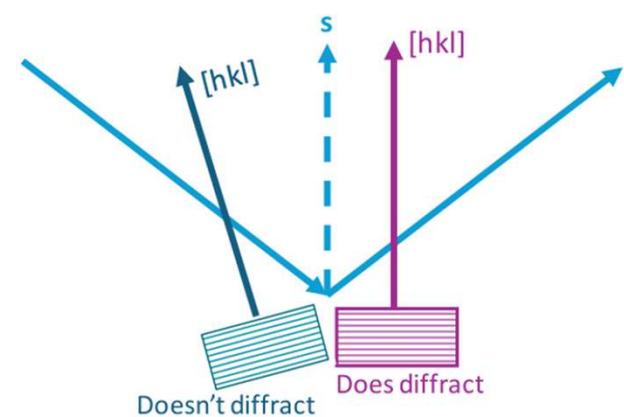
Parallel Beam Geometry

- Parabolic Mirror
- Parallel Plate Collimator
 - Narrow Acceptance Angle
- Point Detector

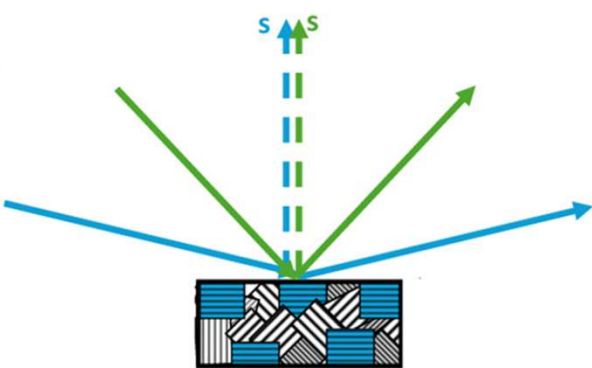


Introduction to Grazing Incidence

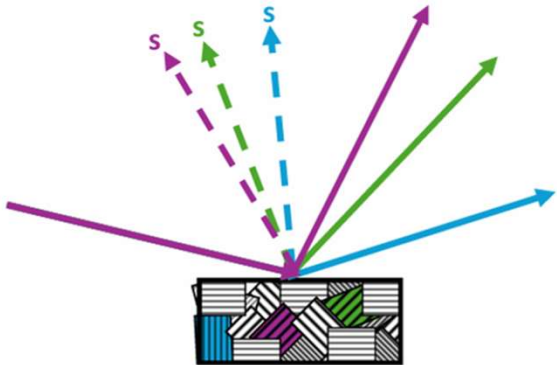
Effect on Preferred Orientation



- In a powder diffractometer, diffraction from a crystal is only observed if:
 - The detector is at the Bragg angle
 - The diffraction vector $\mathbf{s}$ is parallel to the crystallographic direction $[hkl]$



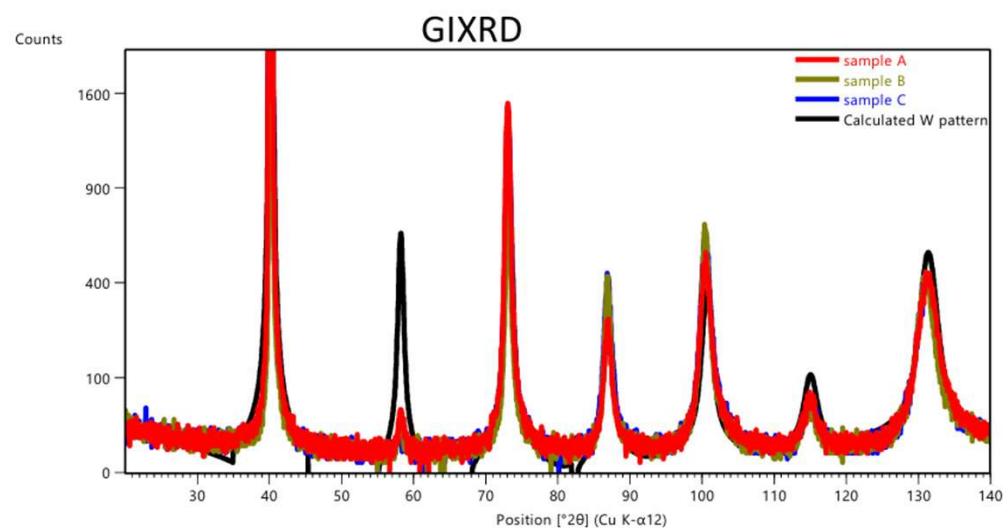
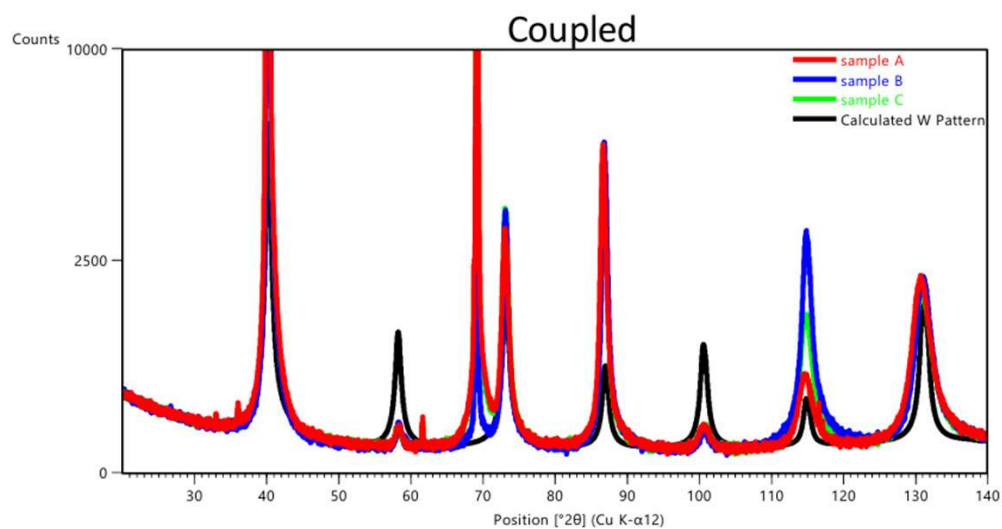
- In Bragg-Brentano geometry, the diffraction vector $\mathbf{s}$ does not change during the measurement
- Every observed diffraction peak is produced by $[hkl]$ oriented in the sample direction



- In GIXRD geometry, the diffraction vector $\mathbf{s}$ changes with the detector angle 2θ
- Every observed diffraction peak is produced by $[hkl]$ oriented in a different direction

Introduction to Grazing Incidence

Effects on Texture

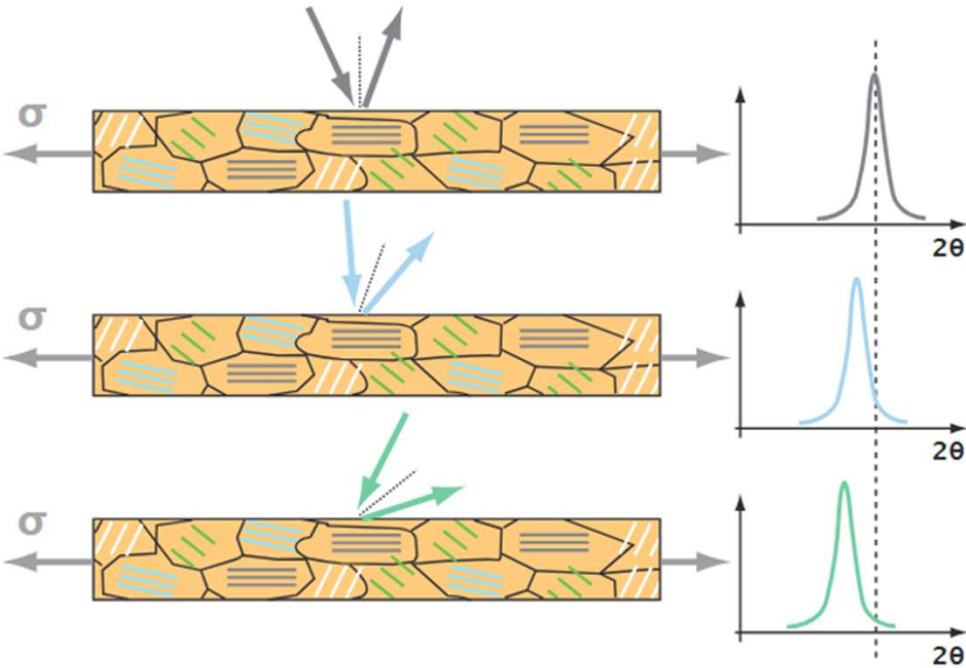


Introduction to Grazing Incidence

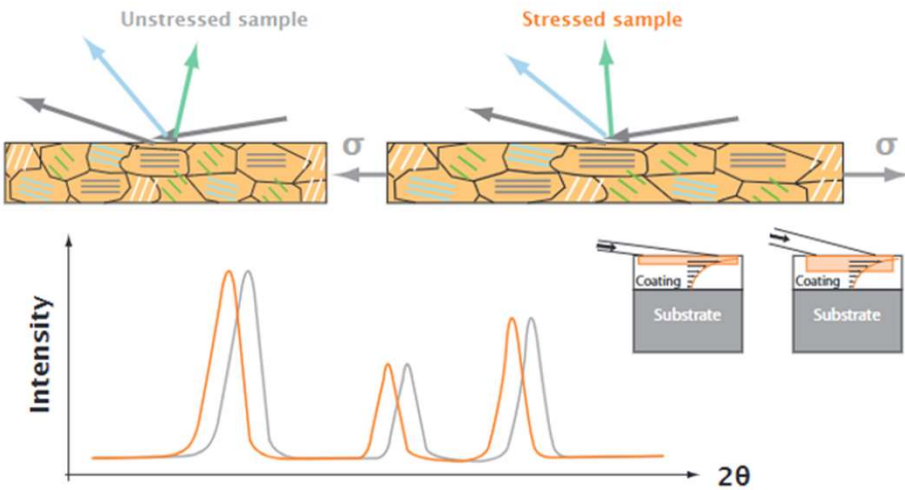
Multi- $\{hkl\}$ Residual Stress



Classic Residual Stress

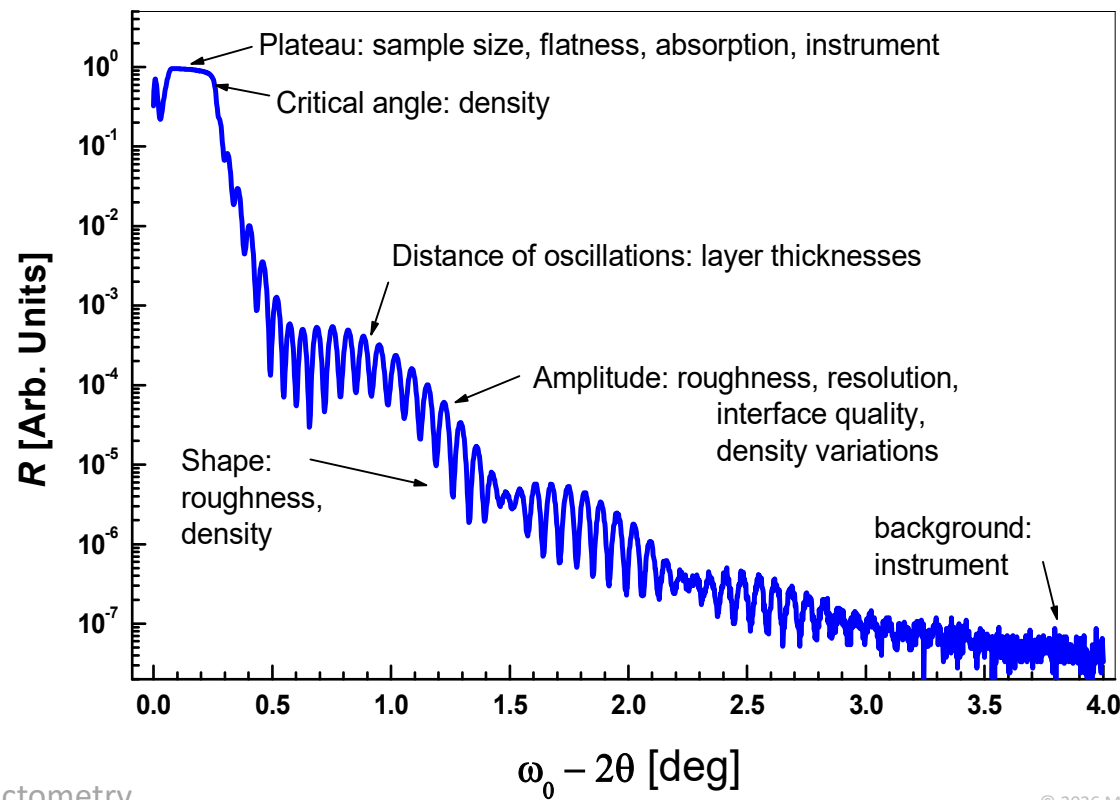


GI Stress



Introduction to X-Ray Reflectivity

Overview of Observed Data

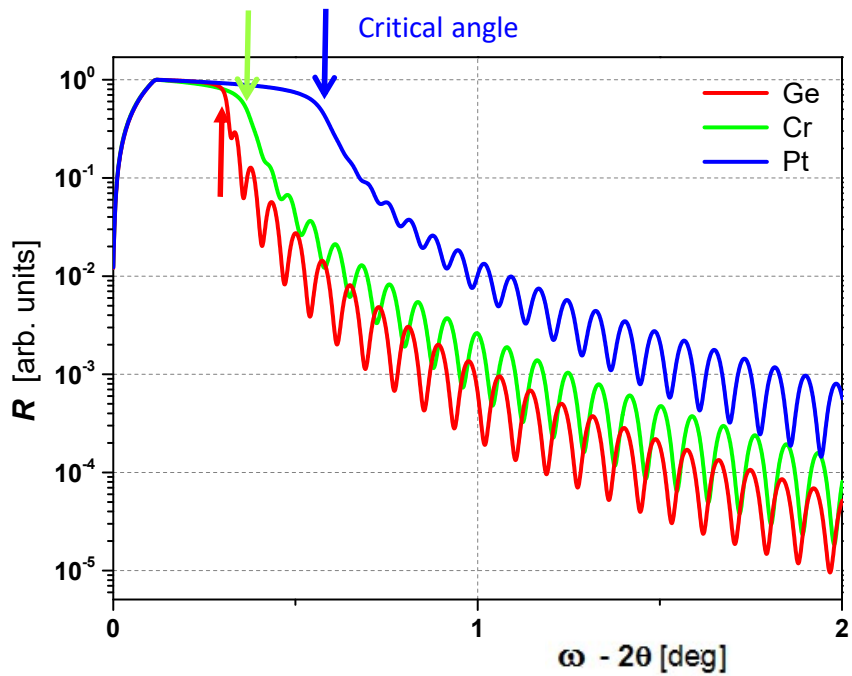


Introduction to X-Ray Reflectivity

Effect of Layer Density



The reflectance of 50 nm single layer on a Si substrate:



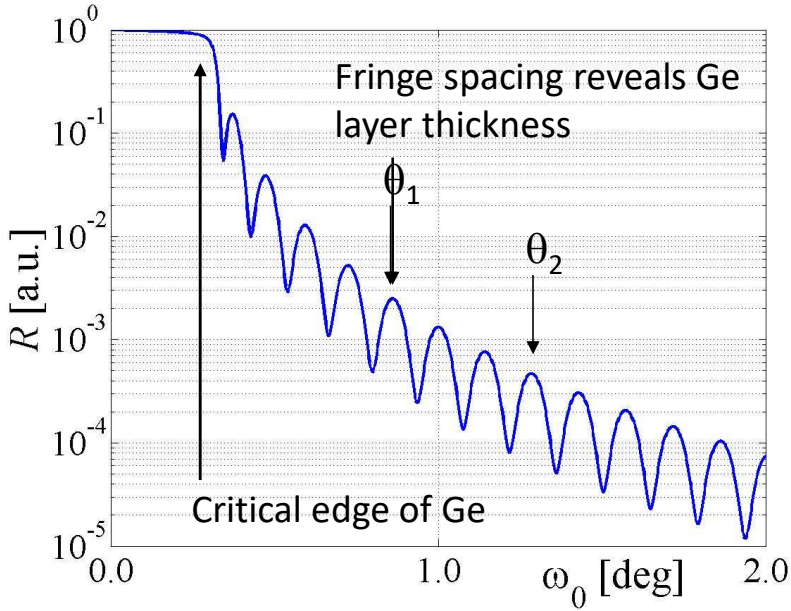
Critical angle Density

$$\omega_C \sim \sqrt{\rho}$$

$\omega_0 < \omega_c$, total reflection

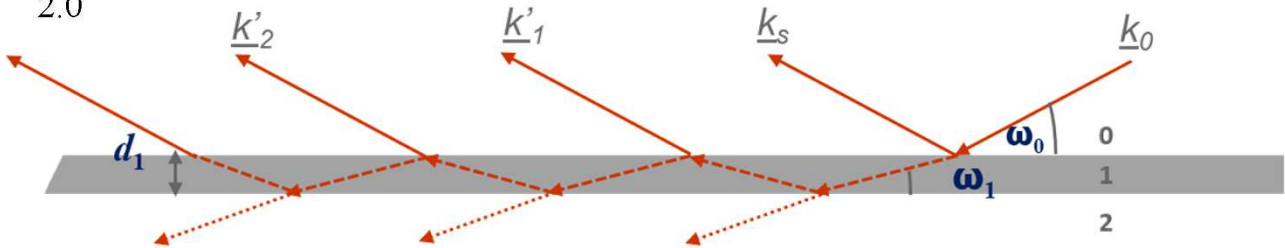
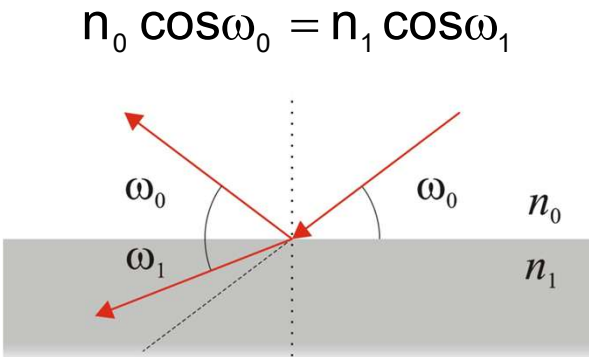
Introduction to X-Ray Reflectivity

Film Thickness



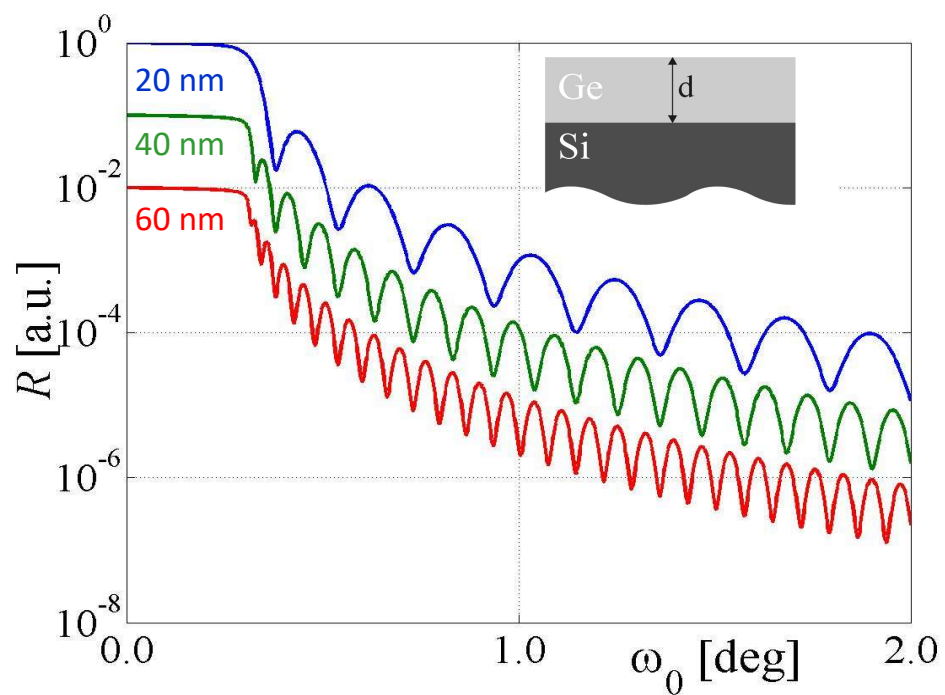
Example: 30 nm Ge layer on Si substrate

$$d = \frac{M\lambda}{2(\sqrt{\theta_1^2 - \omega_c^2} - \sqrt{\theta_2^2 - \omega_c^2})}$$



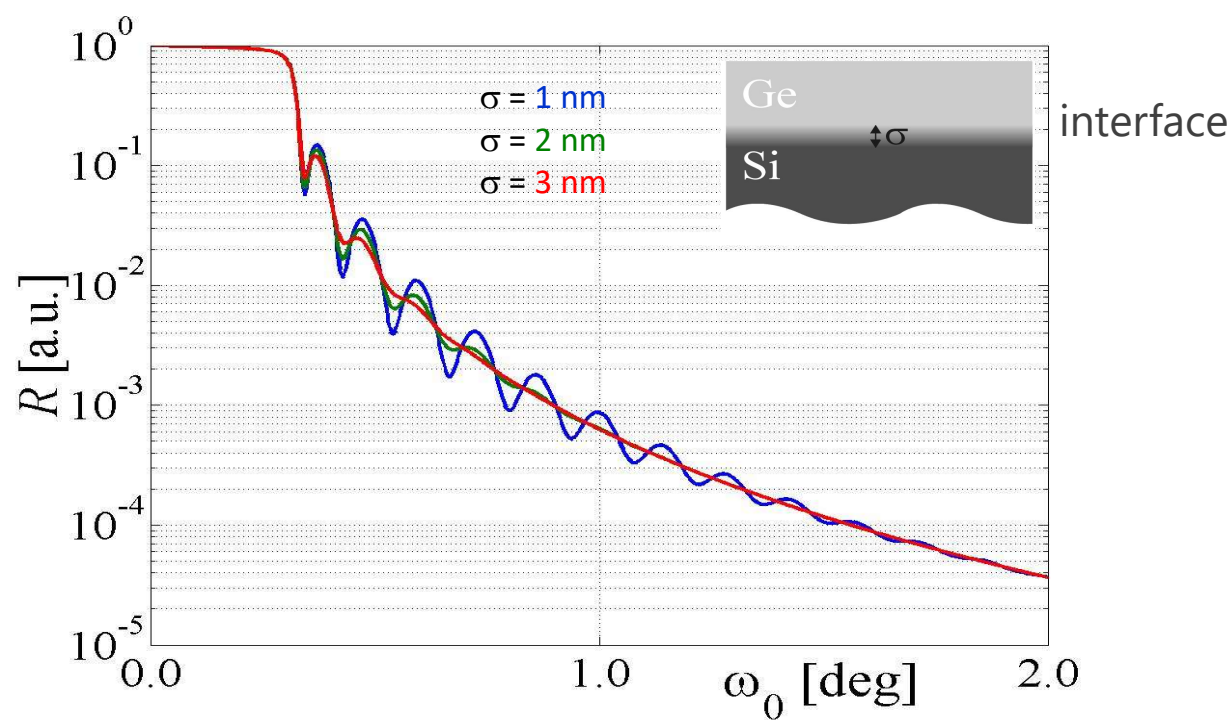
Introduction to X-Ray Reflectivity

Effect of Layer Thickness



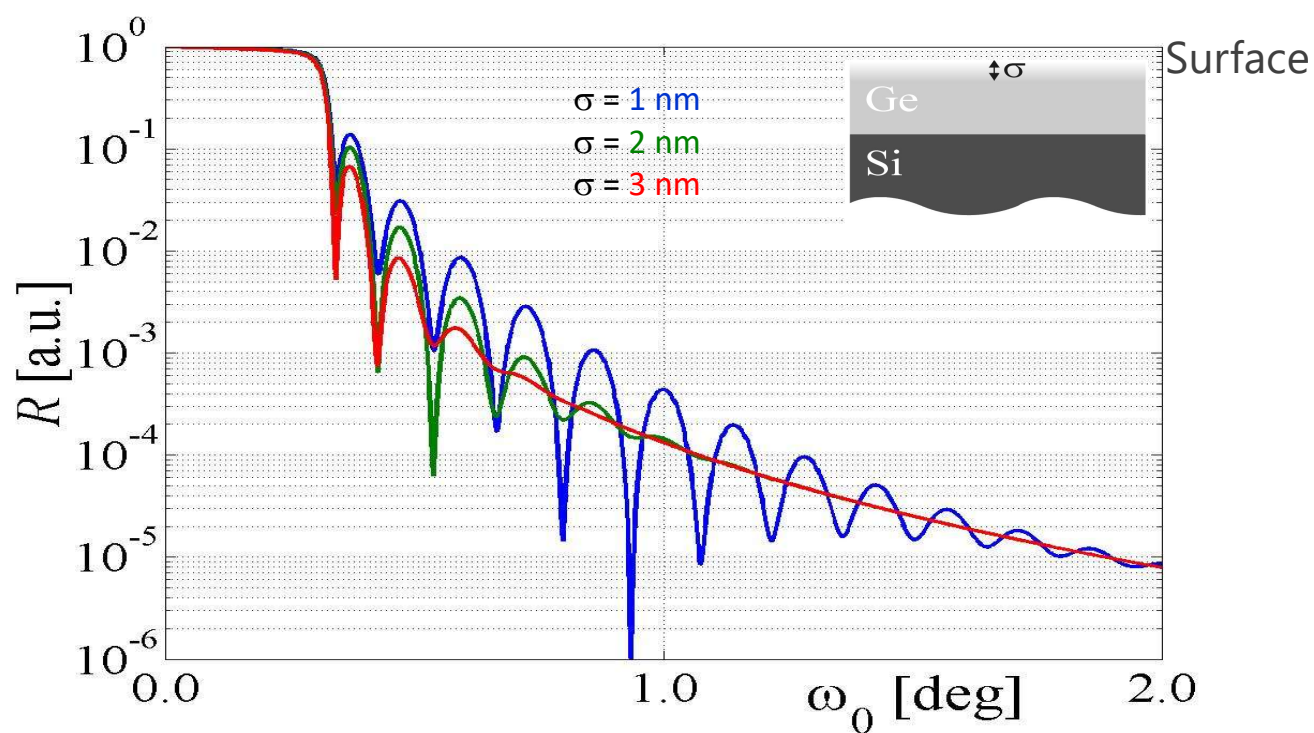
Introduction to X-Ray Reflectivity

Effect of Layer Roughness



Introduction to X-Ray Reflectivity

Effect of Layer Roughness



Introduction to GI-XRD and XRR

Summary



- Grazing incidence can be used for polycrystalline thin films to obtain a wide range of “standard” powder diffraction information about the surface layer. These include:
 - Phase Identification
 - Crystallite Size and Strain
 - Residual Stress
 - Depth Profiling
- X-Ray reflectivity provides information more specific to the film structure:
 - Density
 - Thickness
 - Surface and Interface Roughness